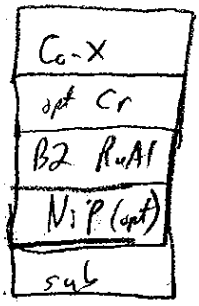
Seagate

3/7/01
12/20/01

10/022,728



(11.0) crystal

oxidized, textured

spec
- Replacement ~~Rep~~ ~~page~~ Y+S w/6 highlights
- "SEA 2758" - replace with U.S. Patent ~~Office~~ Serial Number

admissions
- OR ~1.5 have > S/N ratio than OR=1.0
- Cr (200) promotes Co (11.0)
  B2 (200)

~~742~~ A1
102 : c1, 3, 6, 9, 10 – 16, 20
103 : c2 (sub = mech. textured ; OR ~ 1.05)
c4 ~~17~~ 19 (oxidized NiP on non-metalic substrate)
c5 (surface oxidize NiP on Al-alloy substrate)
~~19~~ 17 c7 4 (12-50 at% P, 0.5-50 at% surface oxygen)
c8 7 (NiP = 50-200,000 Å)
c18 (elect. plated oxidized NiP on Al-alloy, plus textured)

c2) ito Lal et al – Okumura et al
c4, 7, 8, 17, 19) ito Chen et al '795 + Chen et al '370
c5 ~~18~~, ito Chen et al (x2) above + Obana et al - 949 A1
c18) as c5 + ito Okumura et al + Lal et al

ate – Jones et al, Cao et al, Kanda et al

• Equiv. of glass to NiP/Al
• texture of NiP → motion
• OR 1.4-1.6 motion

(cite)

Kanbe '796 Al

Benefits of circum. texture

(cite)

Sones '809

• OR > 1.5 as desired for long. textured
• textured substrate inc. NiP/Al (thinner) or glass

Lal et al '924

Oxidizing conditions

Chen et al '370

(cite)

• Equiv. of substrates
• Equiv. of plating/sputtering
• texture NiP induces anisotropy
• control anisotropy to 0.95 - 1.10

(cite)

Coo '033

• equiv. of sputter or plating
• effect on OR of texture
• motion to texture

Okumura 1733

NiP_3 (25% P)

Co-alloy (11x0)
Cr
B2 (200)
Cr (base)
surface Ox. NiP
Sub

Chen et al '795

longitudinal media
• NiP oxidized - motion and textured - motion

Co (1120)
Cr (200)
oxid NiP
Sub

Abarra '949 Al